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a third step of depositing an organic film by a CVD method onto substantially all exposed surfaces of said substrate, provided with said scintillator, introduced into said vapor deposition chamber in a state that said substrate is supported so as to maintain a distance from said rotatable vapor deposition table.

Please add the following new claims:

8. (New) An organic film vapor deposition method according to claim 1, wherein the rotatable vapor deposition table comprises a turntable.

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9. (New) An organic film deposition method according to claim 1, where the third step of depositing the organic film is performed while the vapor deposition table is rotating.

10. (New) An organic film vapor deposition method according to claim 8, further comprising a fourth step of depositing a second organic film by a CVD method onto substantially all exposed surfaces of the organic film deposited in the third step.

11. (New) An organic film vapor deposition method according to claim 10, wherein the fourth step comprises supporting the substrate, after having the organic film deposited in the third step formed thereon, on at least three protrusions of a target-support element disposed on the rotatable vapor deposition table, with the support positions of the protrusions in the fourth step being shifted with respect to the support positions of the protrusions in the first step.

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